

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

---

Patent Application of:

Toshihiko OHASHI et al.

Application No.: 10/541,776

Confirmation No.: 1474

Filed: July 08, 2005

Art Unit: 1794

For: SILICA-CONTAINING LAMINATED  
STRUCTURE, AND COATING  
COMPOSITION FOR USE IN FORMING A  
POROUS SILICA LAYER

---

Examiner: V. CHANG

**STATEMENT OF THE SUBSTANCE OF THE INTERVIEW**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Applicant submits the following statement on the substance of the interview held on  
June 16, 2010.

The description of the telephonic interview as given by the Examiner on the Interview  
Summary Form adequately describe the details of the telephonic interview.

If necessary, the Director is hereby authorized in this, concurrent, and future replies to charge any fees required during the pendency of the above-identified application or credit any overpayment to Deposit Account No. 02-2448.

Dated:

JUL 12 2010

Respectfully submitted,

By 

John W. Bailey

Registration No.: 32881

BIRCH, STEWART, KOLASCH & BIRCH, LLP

8110 Gatehouse Road, Suite 100 East

P.O. Box 747

Falls Church, VA 22040-0747

703-205-8000